

論文

2019.3.31.現在

計22件

3件

<平成30年度>

May Thu Zar Myint,Masaki Hada,Hiroataka Inoue,Tatsuki Marui,Takeshi Nishikawa,Yuta Nishina,Susumu Ichimura, Masayoshi Umeno,Aung Ko Ko Kyaw and Yasuhiko Hayashi
 "Simultaneous improvement in electrical conductivity and Seebeck coefficient of PEDOT:PSS by N₂pressure-induced nitric acid treatment"
 RSC Adv.,2018,8, 36563-36570

名倉あずさ, 富永雄一, 今井祐介, 堀田裕司, 伊藤美智子, 高島成剛
 "プラズマ処理による炭素繊維-ポリプロピレン樹脂界面の密着性向上とその経時変化"
 成形加工, Vo. 30, No. 9, pp. 475-478, 2018.

Akihiro Sakatoku, Takuya Fujimura, Michiko Ito, Seigo Takashima, Tadashi Isshiki
 "Newly isolated bacterium nacibaculum sp. strain Pbs-1 from diseased pearl oysters is associated with black-spot shell disease"
 Aquaculture 493 (2018) 61-67.

<平成29年度>

1件

Eri Miura-Fujiwara, Yuu Suzuki, Michiko Ito, Motoko Yamada, Sinpei Matsutake, Seigo Takashima, Hisashi Sato and Yoshimi Watanabe
 "Effects of shot-peening and atmospheric-pressure plasma on aesthetic improvement of Ti-Nb-Ta-Zr alloy for dental applications"
 Jpn. J. Appl. Phys. Vol. 57, pp. 01AG05, 2018.

<平成28年度>

1件

Michiko Ito, Tomohiro Takahashi, Sho Takitou, Seigo Takashima, Norio Nomura, Tominori Kitagawa and Hiroataka Toyoda
 "Enhancement of Liquid Treatment Efficiency by Microwave Plasma under Flow-Induced Reduced Pressure"
 Jpn. J. Appl. Phys. Vol. 56, pp. 026201, 2017.

<平成25年度>

1件

岡真佐人, 浅野浩志, 北原路郎, 中田悟, 伊藤美智子, 高島成剛, 浅見悦男, 青木猛, 山口浩一, 村瀬由明
 "微粒子酸化チタンの水中分散に関する液面プラズマの影響"
 粉体工学会誌, 50, 840-844(2013)

<平成24年度>

4件

M. Ito, M. Hayakawa, S. Takashima, E. Asami, T. Aoki, M. Oka, H. Asano, M. Kitahara, S. Nakata, K. Yamaguchi, and Y. Murase
 "Preparation of Aqueous Dispersion of Titanium Dioxide Nanoparticles using Plasma on Liquid Surface"
 Jpn. J. Appl. Phys. Vol. 51, pp. 116201, 2012.

M. Inoue, T. Ohta, N. Takota, S. Tsuchitani, S. Takashima, K. Yamakawa, H. Kano, K. Takeda, M. Hori, and M. Ito
 "Properties of Indium-Zinc-Oxide Films Synthesized by Radio Frequency Magnetron Sputtering Based on Gas Phase Monitoring Using Multi-Micro Hollow Cathode Lamp"
 Jpn. J. Appl. Phys. Vol. 51, pp.116202, 2012.

M. Inoue, T. Ohta, N. Takota, S. Tsuchitani, M. Ito, S. Takashima, H. Kano, K. Yamakawa, K. Takeda, and M. Hori
 "Line-Profiles and Translational Temperatures of Pb Atoms in Multi-Micro Hollow Cathode Lamp Measured by Diode Laser Absorption Spectroscopy"
 Jpn. J. Appl. Phys. Vol. 51, pp. 086301, 2012.

S. Takahashi, R. Kawauchi, S. Takashima, S. Den, T. Katagiri, H. Kano, T. Ohta, M. Ito, T. Suzuki, K. Takeda, M. Hori
 "An Autonomously Controllable Plasma Etching System Based on Radical Monitoring"
 Jpn. J. Appl. Phys. Vol. 51, pp. 076502, 2012.

論文

2019.3.31.現在

<平成23年度>

2件

T. Yamaguchi, T. Komuro, C. Koshimizu, S. Takashima, K. Takeda, H. Kondo, K. Ishikawa, M. Sekine, M. Hori
 "Direct current superposed dual-frequency capacitively coupled plasmas in selective etching of SiOCH over SiC"
 J. Phys. D: Appl. Phys. Vol. 45, pp. 025203, 2011.

K. Takeda, Y. Miyawaki, S. Takashima, M. Fukasawa, K. Oshima, K. Nagahata, T. Tatsumi and M. Hori
 "Mechanism of plasma-induced damage to low-k SiOCH films during plasma ashing of organic resists"
 J. Appl. Phys. Vol. 109, pp. 033303, 2011.

<平成22年度>

3件

S. Takashima, K. Takeda, S. Kato, M. Hiramatsu and M. Hori
 "Surface Loss Probability of Nitrogen Atom on Stainless-Steel in N₂ Plasma Afterglow"
 Jpn J. Appl. Phys. Vol.49, pp. 076101, 2010.

Chang S. Moon, K. Takeda, S. Takashima, M. Sekine, Y. Setsuhara, M. Shiratani and M. Hori
 "Surface loss probabilities of H and N radicals on different materials in afterglow plasmas employing H₂ and N₂ mixture gases"
 J. Appl. Phys. Vol.107, pp. 103310, 2010.

Chang S. Moon, K. Takeda, S. Takashima, M. Sekine, Y. Setsuhara, M. Shiratani and M. Hori
 "High performance of compact radical monitoring probe in H₂/N₂ mixture plasma"
 J. Vac. Sci. Technol. B 28, pp. L17, 2010.

<平成21年度>

2件

S. Takahashi, S.Takashima, K.Yamakawa, S. Den, H.Kano, K. Takeda and M. Hori
 "Development of atomic monitoring probe and its application to spatial distribution measurements of H and O atomic radical densities in radical-based plasma processing"
 J. Appl. Phys. Vol.106, pp. 053306, 2009.

W. Takeuchi, H. Sasaki, S. Kato, S. Takashima, M. Hiramatsu and M. Hori
 "Development of measurement technique for carbon atoms employing vacuum ultraviolet absorption spectroscopy with a microdischarge hollow-cathode lamp and its application to diagnostics of nanographene sheet material formation plasmas"
 J. Appl. Phys. Vol. 105, pp. 113305, 2009

<平成20年度>

5件

M. Fukasawa, T. Tatsumi, K. Oshima, K. Nagahata, S. Uchida, S. Takashima, M. Hori and Y. Kamide
 "Surface Reactions during Low-k Etching using N₂/H₂ Plasma"
 J. Vac. Sci. Technol. A 26, pp. 870, 2008.

K. Takeda, S. Takashima, M. Ito and M. Hori
 "Absolute Density and Temperature of O(¹D₂) in Highly Ar or Kr Diluted O₂ Plasma"
 Appl. Phys. Lett. Vol. 93, pp. 021501, 2008.

T. Ideno, H. Inui, S. Takashima, H. Kano, M. Kondo, M. Hiramatsu and M. Hori
 "Novel Silicon Wafer Slicing Technology Using Atmospheric-Pressure Reactive Microplasma"
 Jpn. J. Appl. Phys. Vol. 47, pp. 5648, 2008.

S. Uchida, S. Takashima, M. Hori, M. Fukasawa, K. Ohshima, K. Nagahata and T. Tatsumi
 "Evaluation of Property Changes due to Radiation, Radicals and Ions on Organic Low-k Films in H₂/N₂ Plasma Etching"
 Jpn. J. Appl. Phys. Vol. 47, pp. 3621, 2008.

S. Uchida, S. Takashima, M. Hori, M. Fukasawa, K. Ohshima, K. Nagahata and T. Tatsumi
 "Plasma Damage Mechanisms for Low-k Porous SiOCH Films due to Radiation, Radicals and Ions in the Plasma Etching Process"
 J. Appl. Phys. Vol. 103, pp. 073303, 2008.